

**Notice of References Cited**

Application/Control No.

10/027,533

Applicant(s)/Patent Under  
Reexamination  
HARTNER ET AL.

Examiner

Brian K Talbot

Art Unit

1762

Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,970,309	10-1999	Ha et al.	438/3
*	B	US-5,320,978	06-1994	Hsu, David S. Y.	438/606
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	222,711	08-1996	Japan		
	O	289,291	11-1997	Japan		
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	Xue et al., "Organometallic Chemical Vapor Deposition of Platinum Reaction Kinetics and Vapor Pressures of Precursors", Chem. Material. 1992, No. 4, pp.162-166.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.